

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Wang	
Application No.: 10/723,746	Art Unit: 1765
Filed: 11/25/2003	Examiner: L. Umez Eronini
Title: POLISHING COMPOSITION FOR CMP HAVING ABRASIVE PARTICLES	
Attorney Docket No.: 03049US	

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE

Do Not Enter
Amendment

L.T.M-E
3/25/2006

Dear Sir:

In response to the Office Action of December 22, 2005, having a shortened statutory
deadline of March 22, 2006, please amend this application as follows:

*Entered
URCE
4/17/06
WM.*